

REMARKS


When allowing claims 2-20 from this application's parent application, the examiner acknowledged that the prior art does not teach or suggest forming on a dielectric layer a sacrificial layer for taking in impurities, which is subsequently removed. The pending claims reflect methods for forming a sacrificial layer on a dielectric layer, then removing it prior to forming a gate electrode on the dielectric layer, and methods for removing impurities from a high-k gate dielectric layer prior to forming a gate electrode on the high-k gate dielectric layer. As with previously allowed claims 2-20, the prior art does not teach or suggest the methods of these pending claims. Accordingly, applicants respectfully request the examiner to allow pending claims 21-38 to issue.

If there are any additional charges, please charge Deposit Account No.
02-2666

Respectfully submitted,

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